



AF/2812
10/Response
17/63/01
A. Walker
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JUL 23 2001
TECHNICAL CENTER 2000

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Chandra V. Mouli

§ Group Art Unit:

2812

Serial No.: 09/379,092

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Filed: August 23, 1999

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Examiner:

R. Pompey

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For: FORMING SIDEWALL OXIDE
LAYERS FOR TRENCH
ISOLATION

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Atty. Dkt. No.: MICT-0042-US

Box AF

Commissioner for Patents

Washington DC 20231

REPLY TO FINAL REJECTION

Sir:

In response to the office action mailed June 28, 2001,
please consider the following remarks.

Remarks

Claims 1 and 33 stand rejected under §102 based on the
reference to Hong. (The taking of official notice was only with
respect to the §103 rejection of the dependent claims.)

Reconsideration of the §102 rejection of claims 1 and 33 is
requested. Claim 1 calls for implanting impurities which
enhance the oxidation of said structure beyond that which would
be expected from crystallographic damage effects. The final
rejection states that "Hong is silent on what produces the
oxidation enhancement by implanting dopant species into the
substrate. Therefore, it is not disclosed whether it is
crystallographic damage . . ." In view of this statement, it is
clear that the §102 rejection of claim 1 is not appropriate.

Date of Deposit: 7/16/01
I hereby certify under 37 CFR 1.8(a) that this correspondence is
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Lisa O'Sullivan